

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L1	10	"6258679"	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/03/25 14:55
L2	5	1 and (aqueous or solution or HF)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/03/25 14:11
L3	3	"6316370"	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/03/25 14:10
L4	3	3 and (aqueous or solution or HF)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/03/25 14:11
L5	0	1 and acic	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/03/25 14:56
L6	3	1 and acid	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/03/25 14:57
L7	1	6 and HF	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/03/25 14:57
L8	498	7 and water and wet eching	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/03/25 14:58

L9	1	7 and (water or wet etching)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/03/25 15:03
L10	24	"5532182"	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/03/25 15:06
L11	34	"5637523"	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/03/25 15:06
L12	47	10 or 11	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/03/25 15:06
L13	44	12 and (HF or acid or water or deionized or Si or SiGe or silicon germanium)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/03/25 15:29
L14	44	13 and (oxide or remov\$4 or etch\$4)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/03/25 15:13
L15	4	14 and (remov\$4 adj1 oxide)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/03/25 15:46
L16	22	"3677848"	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/03/25 15:13

L17	21	16 and (HF or acid or water or deionized or Si or SiGe or silicon germanium)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/03/25 15:29
L18	80	"4649625"	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/03/25 15:29
L19	4	"6558816"	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/03/25 15:29
L20	24	"5692281"	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/03/25 15:29
L21	96	18 or 19 or 20	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/03/25 15:29
L22	91	21 and (HF or acid or water or deionized or Si or SiGe or silicon germanium)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/03/25 15:48
L23	16	22 and (remov\$4 adj1 oxide)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/03/25 15:33
L24	16	16 and ((silicon germanium) or SiGe)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/03/25 16:59

L25	2	"2001351869"	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/03/25 16:10
L26	5	2 and ((silicon germanium) or SiGe)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/03/25 15:46
L27	5	26 and (HF or acid or water or deionized or Si or SiGe or silicon germanium)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/03/25 17:04
L28	2	27 and (remov\$4 adj1 oxide)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/03/25 17:04
L29	2	28 and (HF or acid)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/03/25 15:49
L30	0	29 and hydrofluoric	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/03/25 16:59
L31	2	"6544874"	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/03/25 16:10
L32	16	24 and ((silicon germanium) or SiGe)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/03/25 16:45

L33	12	32 and hydrofluoric	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/03/25 16:33
L34	90	21 and (bottom surface)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/03/25 16:45
L35	3	"2003216041"	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/03/25 16:45
L36	0	35 and ((silicon germanium) or SiGe)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/03/25 16:53
L37	71735	(selectivity selectively selective) near3 etch\$3	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/03/25 16:53
L38	2313	(amorphous adj (si silicon)) near3 (SiFe GeSi ((Ge Germanium) near1 (Si silicon)))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/03/25 17:51
L39	73570	37 or 38	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/03/25 16:58
L40	49842	39 and ((silicon germanium) or SiGe)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/03/25 17:17

L41	19432	40 and ((hydrofluoric acid) or HF)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/03/25 17:17
L42	35	"5277748"	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/03/25 17:01
L43	0	42 and (amorphous adj (si silicon)) near3 (SiFe GeSi ((Ge Germanium) near1 (Si silicon)))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/03/25 17:03
L44	34	42 and (amorphous or silicon or SiFe or GeSi or Ge or Germanium)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/03/25 17:04
L45	34	44 and (HF or acid or water or deionized or Si or SiGe or silicon germanium)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/03/25 17:17
L46	84	34 and ((remov\$4 adj1 oxide) or oxide)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/03/25 17:05
L47	28	45 and ((remov\$4 adj1 oxide) or oxide)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/03/25 17:56
L48	105	"5013681"	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/03/25 17:17

L49	104	48 and ((silicon germanium) or SiGe)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/03/25 17:55
L50	44	49 and ((hydrofluoric acid) or HF)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/03/25 17:49
L51	44	50 and (HF or acid or water or deionized or Si or SiGe or silicon germanium)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/03/25 17:17
L52	43	51 and ((remov\$4 adj1 oxide) or oxide)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/03/25 17:21
L53	55221	(amorphous adj1 silicon) and (SiGe or GeSi or Ge Germanium or si or silicon)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/03/25 17:49
L54	13411	53 and ((hydrofluoric acid) or HF)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/03/25 17:52
L55	22	"3677848"	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/03/25 17:50
L56	25	"4026733"	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/03/25 17:50

L57	28	"4040897"	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/03/25 17:50
L58	96	"4142926"	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/03/25 17:50
L59	31	"4415383"	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/03/25 17:50
L60	13	"4554046"	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/03/25 17:50
L61	29	"4681657"	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/03/25 17:50
L62	55	"4943618"	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/03/25 17:50
L63	166763	55 or 56 or 57 or 58 or "589" or 60 or 61 or 62	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/03/25 17:51
L64	10	63 and (amorphous adj (si silicon)) near3 (SiFe GeSi ((Ge Germanium) near1 (Si silicon)))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/03/25 17:55



L65	4	64 and ((hydrofluoric acid) or HF)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/03/25 17:55
L66	2	"20030062568"	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/03/25 17:55
L67	1	66 and ((hydrofluoric acid) or HF)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/03/25 18:05
L68	1	67 and ((silicon germanium) or SiGe)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/03/25 18:05
L69	1	68 and ((remov\$4 adj1 oxide) or oxide)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/03/25 18:05
L70	7	"4380490"	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/03/25 18:04
L71	3	70 and ((remov\$4 adj1 oxide) or oxide)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/03/25 18:05
L72	3	71 and ((silicon germanium) or SiGe)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/03/25 18:05

L73	3	72 and ((hydrofluoric acid) or HF)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/03/25 18:05
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